

proTherm
FURNACES



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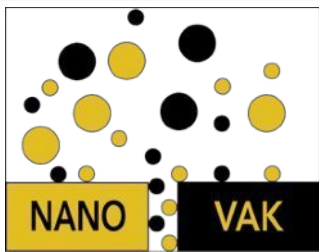
NVPECVD

PECVD Systems

Nanovak Ar-Ge has recently developed PECVD (Plasma Enhanced Chemical Vapor Deposition) tube furnace system, which consists of 300W RF plasma source, optional split tube furnace, 3 channel mass flow controller unit for gases like Ar, H₂, CH₄. It is ideal for Graphene film production as well as TiN, TiC, SiC, Si₃N₄ films.

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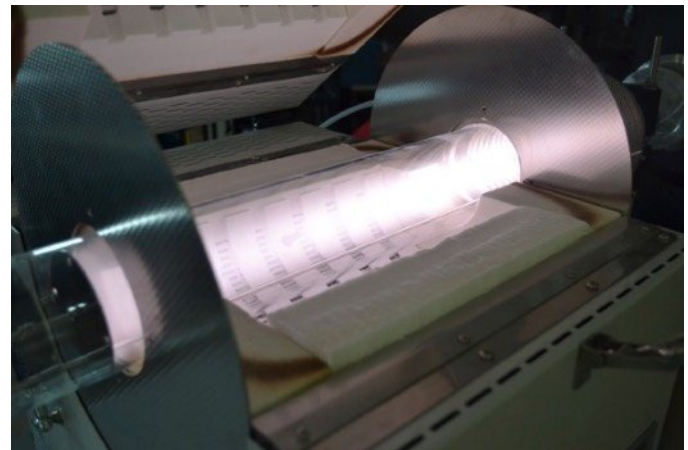
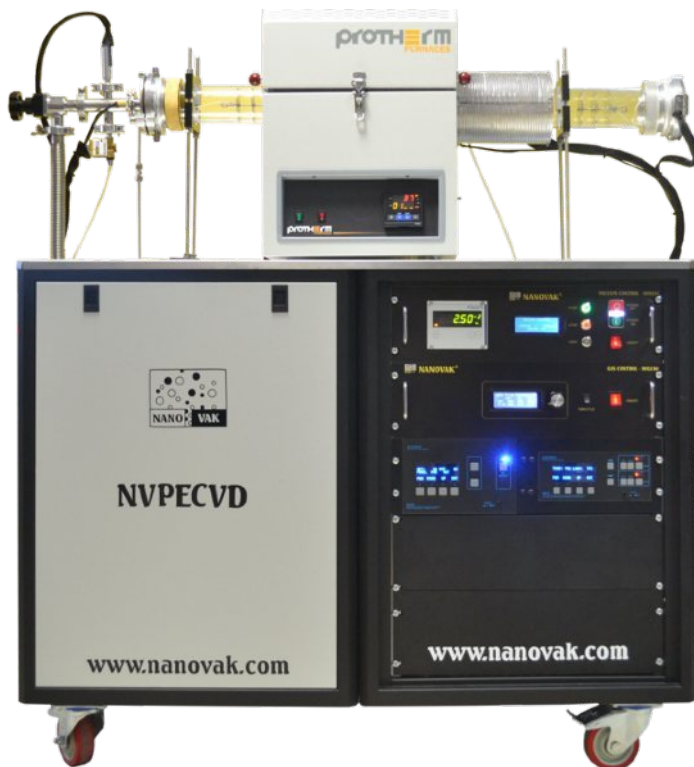
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PECVD Systems



- 1100 °C furnace temperature for continuous heating
- ± 1 °C PID control of furnace temperature
- Split quartz tube (1000 mm long and 50, 80, 100 mm diameter or as desired)
- Automated PLC controlled vacuum control unit. Start, stop and vent buttons.
- PC touch screen control option
- Throttle, vent and isolation valves, precise pressure setting, 1 - 100 mTorr
- User defined programmable heating profiles/steps
- 3 channel, mass flow controller unit for gases like Ar, N₂, O₂, H₂, CH₄, NH₃
- Real time control of all gases, continuous digital display pure or mixed all gas flows
- Option to add 6 more gases
- Inductively coupled 300 W 13.56 MHz plasma source
- Quartz sample holder, plasma is confined to the sample zone
- Easy sample load door
- 220V - 16A power requirement
- Closed cycle water cooling
- 75x120 cm footprint, lockable wheels
- Easy pass through standard doors
- One year warranty for design, materials and workmanship